



Software solutions for  
optimizing micro & nano  
fabrication processes



**NEW: ON-LINE ONLY!!!**

## Invitation with Preliminary Agenda

BEAMeeting 2020 Munich  
March 23<sup>rd</sup> & 24<sup>th</sup>, 2020



Time: Monday 09:00 until 12:00 Online - Training & Workshop  
Monday 13:30 – 17: 00 and Tuesday 9:00 - 12:30 On-Line BEAMeeting  
Tuesday 14:00 LASER lithography session with Heidelberg Instruments

The BEAMeeting is a technical workshop for users and partners of GenISys software products and is free of charge. We are offering on Monday morning on-line training and workshops with GenISys experts. We will start the On-Line BEAMeeting at 13:30 with presentation from GenISys and user. Tuesday afternoon is reserved for a laser session together with Heidelberg Instruments experts. The agenda is still adaptable. We have slots for user on-line presentations. Let us know if you wish to present on your work, or if you wish us to present on a specific subject.

For our planning, please register with an E-mail to [marketing@genisys-gmbh.com](mailto:marketing@genisys-gmbh.com) as soon as possible. We will provide on-line access data for those registering for on-line attendance.

# Preliminary AGENDA

	<b>Monday 23. March</b>	Start
Online Training & Workshop	Session 1: BEAMER – Layout Operation and Fracturing (Basic Training / Workshop)	09:00
	<b>Virtual Coffee Break</b>	10:30
Online Training & Workshop	Session 2: Proximity & Process Calibration and Correction (Advanced Training / Workshop)	11:00
	<b>Virtual Lunch Break</b>	12:30
Nezih Unal GenISys	Welcome & GenISys Update	13:30
Ulrich Hofmann GenISys	Update on TRACER 2.8.0 – Part 1 Application Case: Calibration of HSQ Process	14:00
Thomas Michels GenISys	BEAMER Update New Features and Enhancements	14:30
	<b>Virtual Coffee Break</b>	15:00
Olga Lohse MPI Erlangen	User Presentation	15:30
Qing Tan GenISys	LAB Simulation and OPC User Case: Resolution of 3-4µm at 150µm gap	16:00
Rick Bojko GenISys	Automation of SEM Metrology with ProSEM	16:30
	<b>Tuesday 24. March</b>	
Nit Taksatorn GenISys	E-Beam 3D Simulation including Resist	9:00
Ulrich Hofmann GenISys	Update on TRACER 2.8.0 – Part 2 Application Case: Calibration of HSQ Process	9:30
Qing Tan / Nezih Ünal GenISys	Over-Dose Under-Size (ODUS) Correction using Shape-PEC Application: Single layer lift-off	10:00
	<b>Virtual Coffee Break</b>	10:30
Sylvia Diewald KIT - South	User Presentation	11:20
Daniel Ritter GenISys	Exposure optimization (fracturing, field positioning/ordering, exposure order)	11:40
Thomas Michels	Development Roadmap and Discussion Needs & Wishes	12:00
	<b>Virtual Lunch Break</b>	12:30
Heidelberg Instruments	HIMT Technical Update New Systems & Application	13:30
Christian Pies Heidelberg Instruments	Greyscale Lithography with DWL systems	14:00
Daniel Ritter / Nicola Belic GenISys	BEAMER Correction for Greyscale Lithography	14:20
Holger Sailer IMS Stuttgart	Binary Laser Lithography Correction	14:40
Dmitri Titko GenISys	Rule OPC Calibration and Correction for Laser	15:00
<b>Closing</b>		15:20